

Measurements of PAG cross section to low energy electrons

Steven Grzeskowiak,^a Amrit Narasimhan,^a Jonathan Ostrander,^a and Jonathon Schad,^a
William Earley,^a Robert L. Brainard,^a Leonidas E. Ocola,^b Mark Neisser,^c and Greg
Denbeaux,^a

(a) CNSE

(b) Argonne National Laboratory

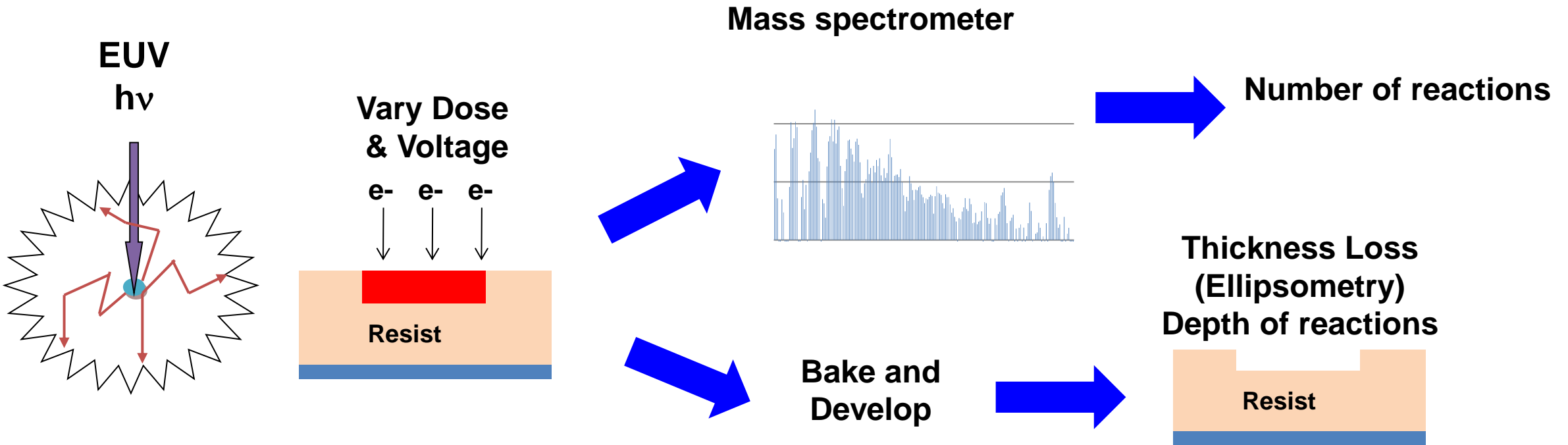
(c) Sematech

Resist TWG meeting
San Jose
February 22, 2015

Overview

- EUV absorption is primarily atomic – composition and density sufficient for good understanding of EUV absorption
- EUV absorption generates primary photoelectrons near 80 eV, which are the primary cause of chemistry in exposed resists.
- Studying electron-PAG reactions and efficiencies will provide insight to help in development of improved resists

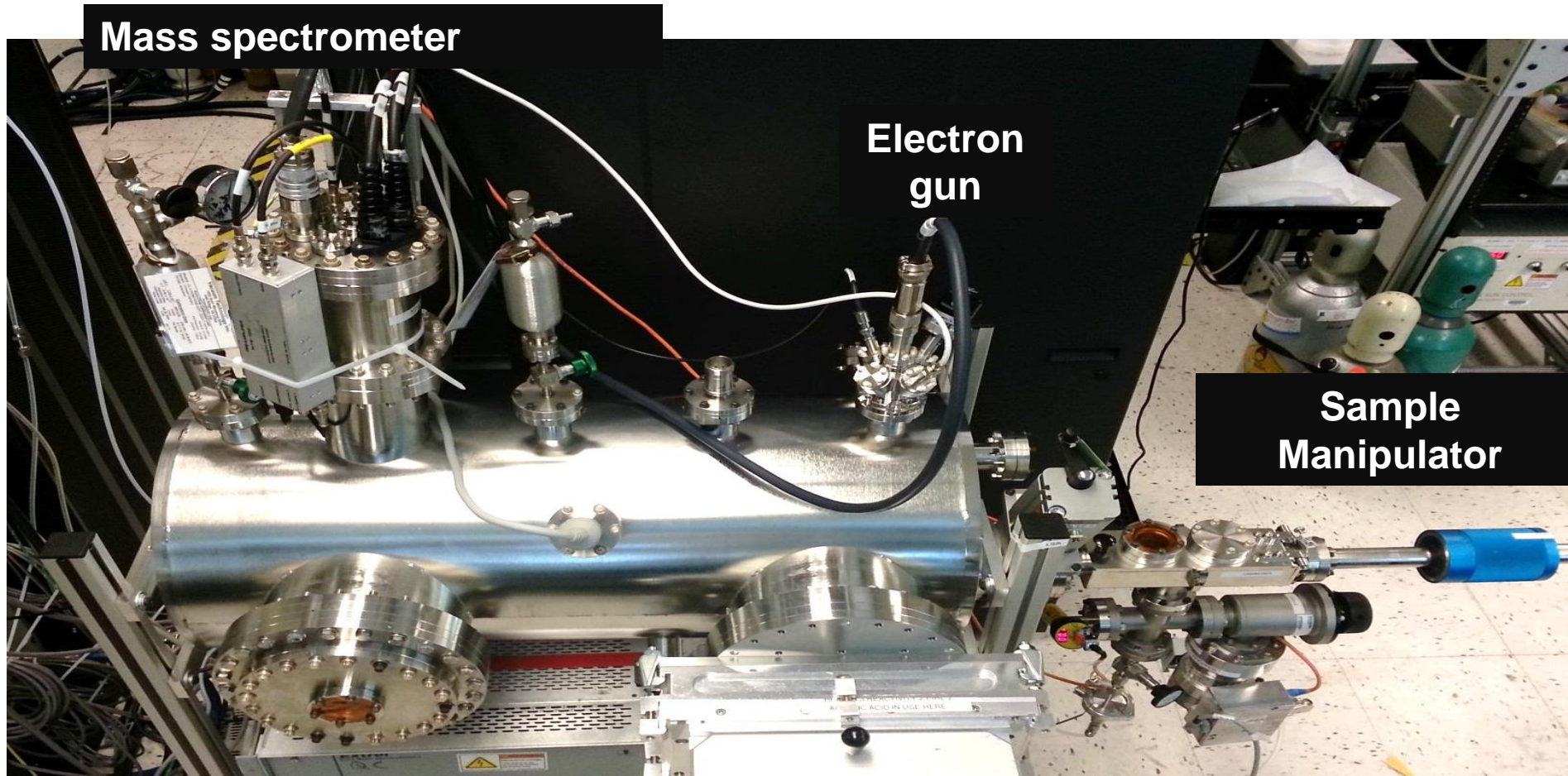
E-beam Reaction rate and depth studies



- From the central absorption event, there will be a maximum range of e^- movement.
- We measure the range by top down exposures and measure the depth to represent the lateral electron travel away from the EUV absorption site.
- We measure number of reactions by mass spectrometry

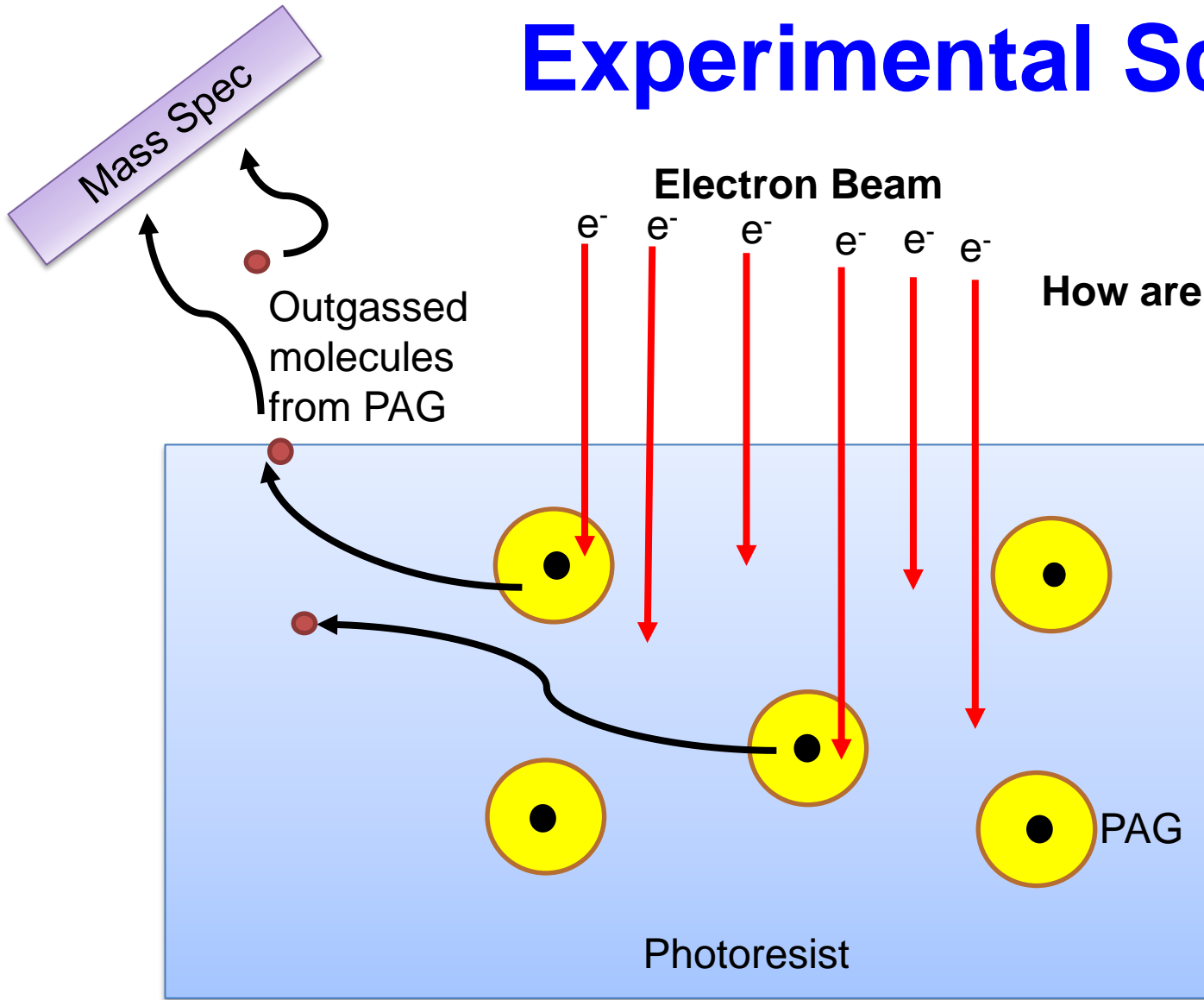
See Narasimhan talk
9422-7 4pm Monday

Electron Resist Interaction Chamber (ERIC)



- Expose EUV resist from 80-2000 eV across a wide range of doses and collect real-time outgassing information using mass spectrometry
- Bake and Develop, then measure the thickness lost with ellipsometry

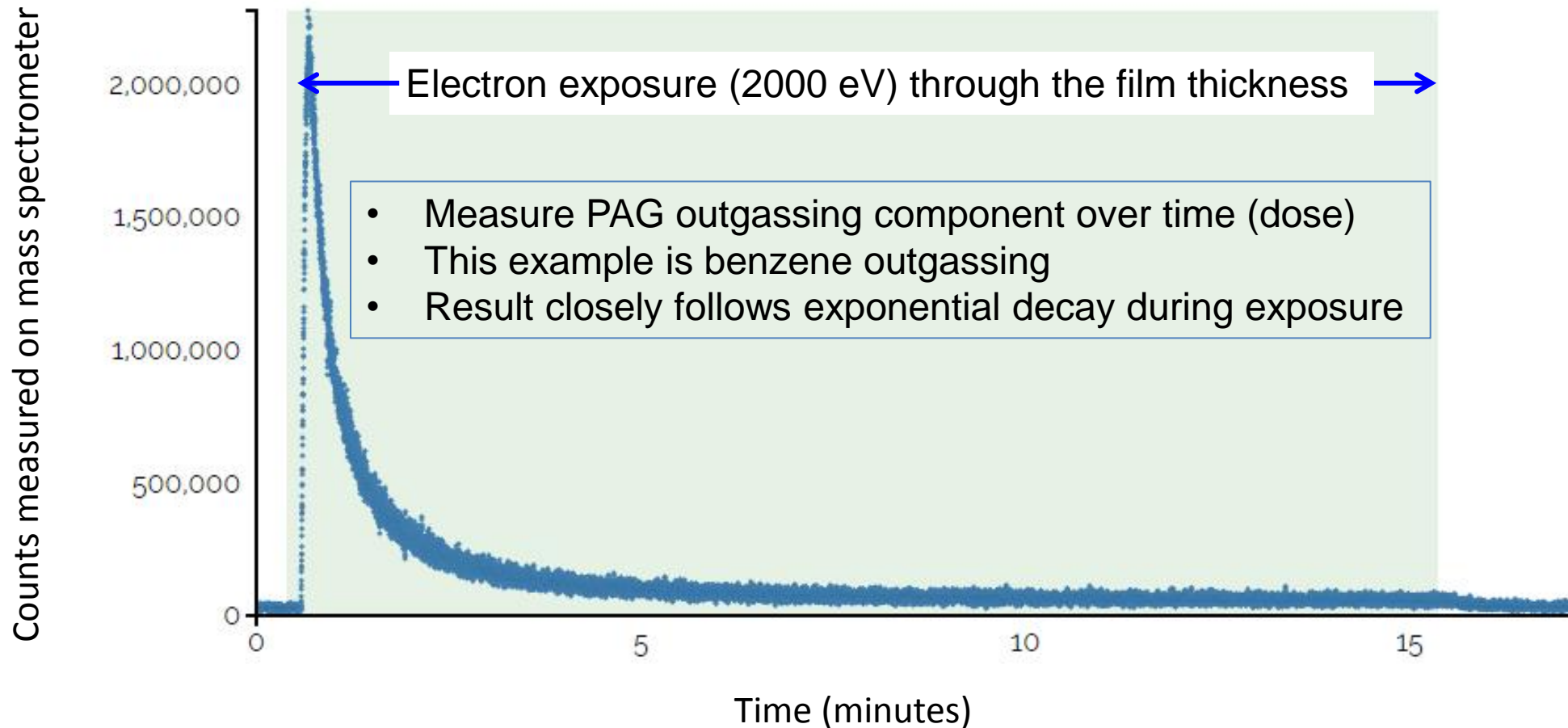
Experimental Schematic



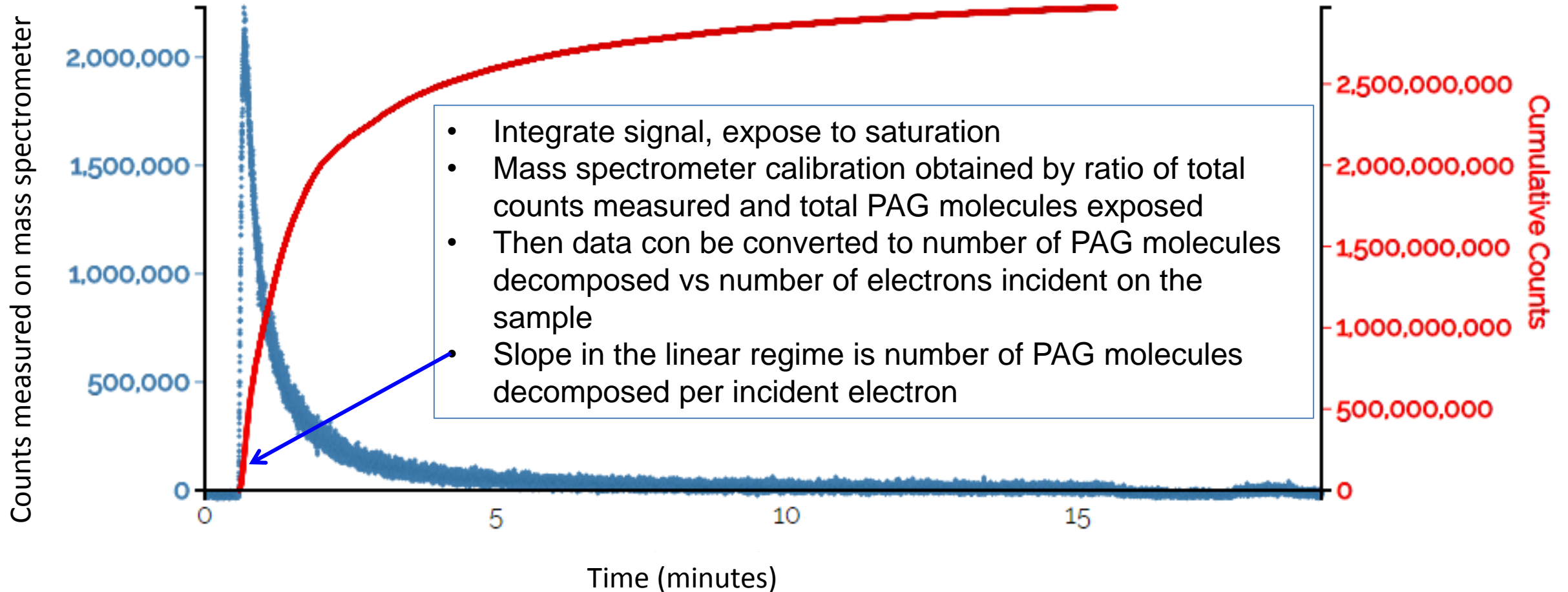
How are we actually measuring #PAG rxns / # e^- ?

Top down electron exposure of photoresist. Molecules outgassed from electron-PAG interactions are monitored using mass spectrometry. (Figure is not to scale.)

PAG reaction measurements

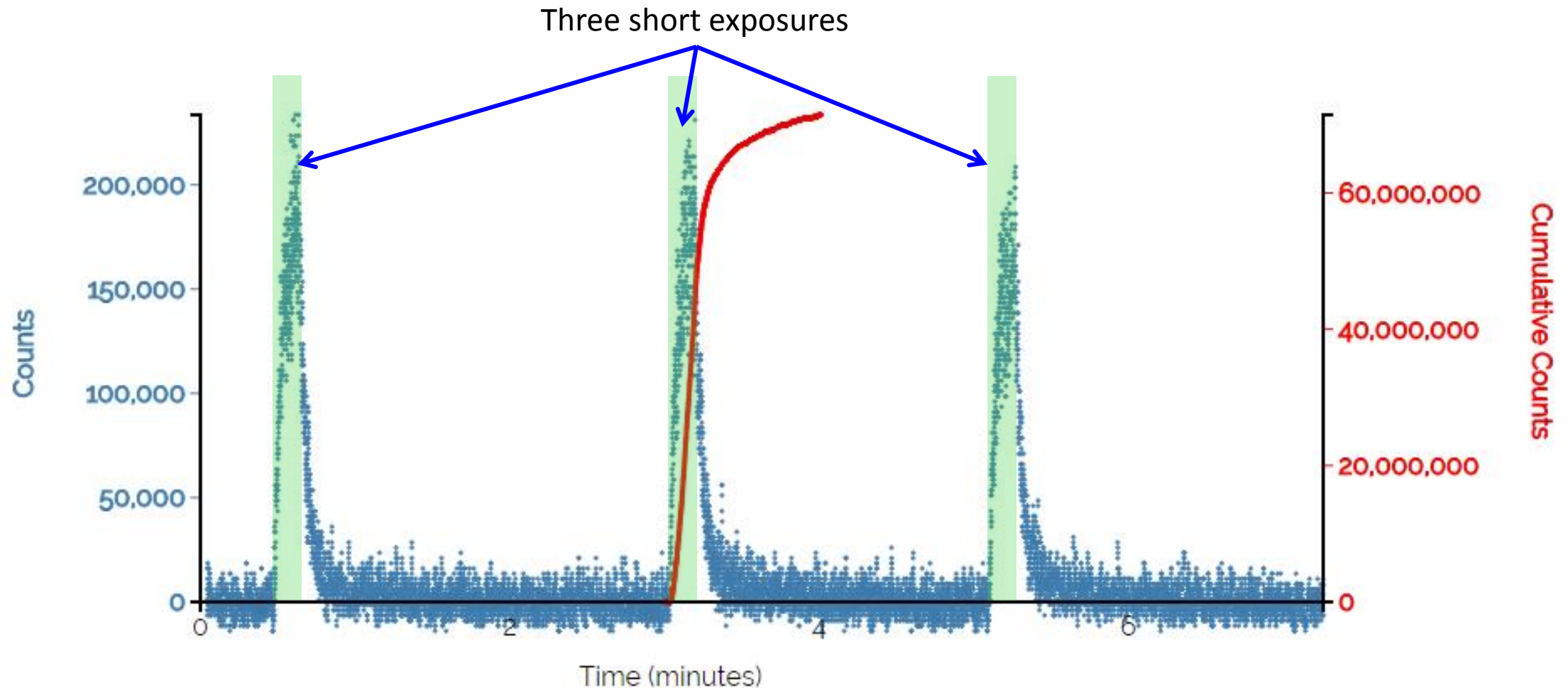


PAG reaction measurements



PAG reaction measurements

For improved accuracy, repeated measurements performed with multiple smaller exposures, each providing number of PAG decompositions per electron after applying the calibration



Resist Formulation and Preparation

Formulation (4 wt.% solids):

1.5 wt.% Base

15 wt.% PAG

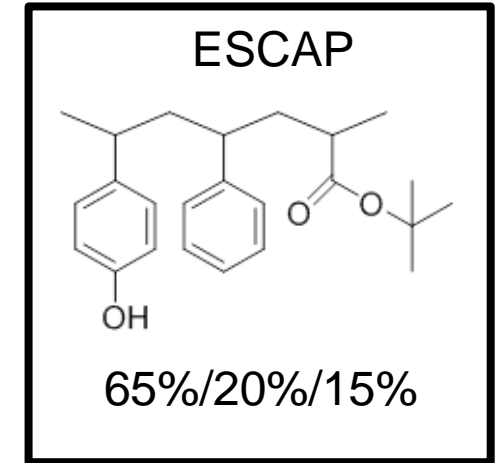
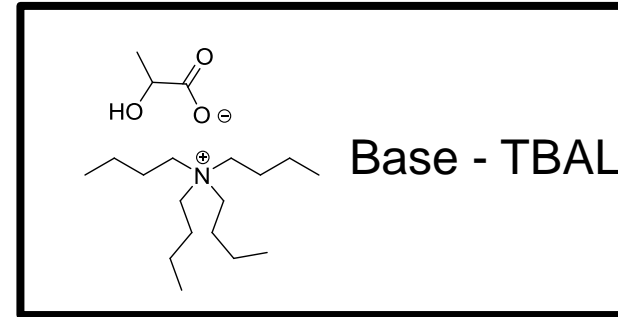
83.5 wt.% Polymer

Spin Coat:

3700 RPM, 45s

Post Application Bake:

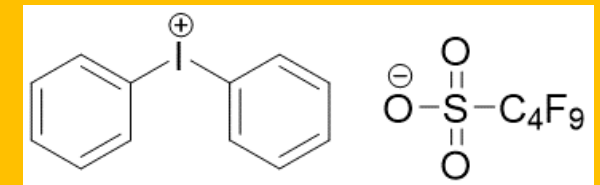
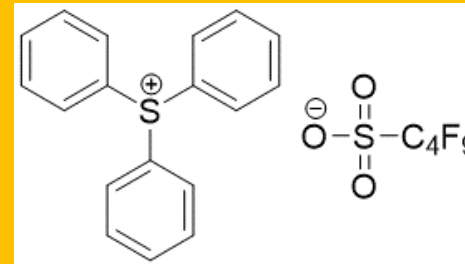
120 °C, 60s



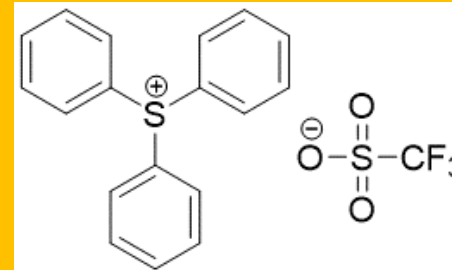
Sulfonium

Iodonium

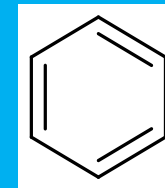
Nonaflate



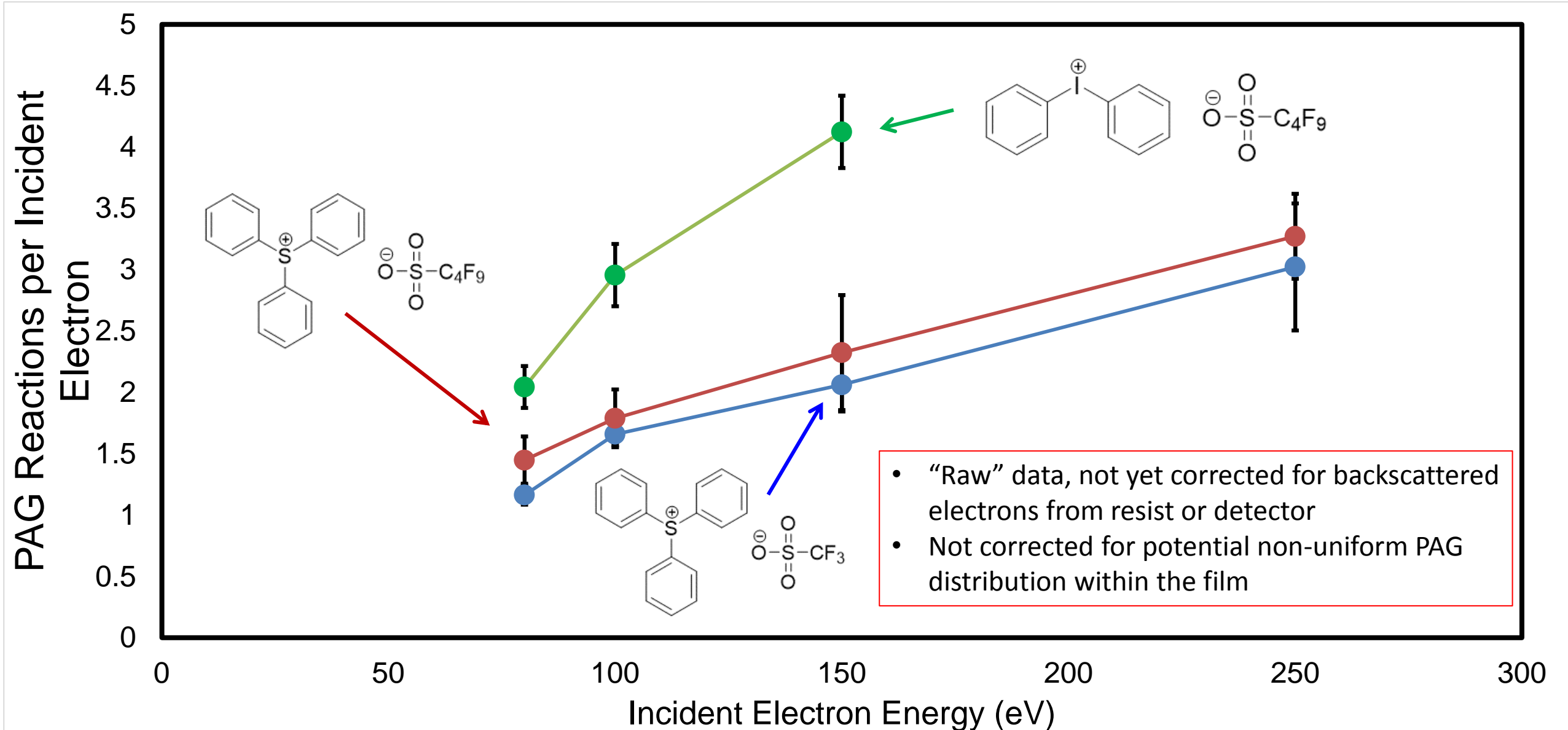
Triflate



All 3 outgas benzene

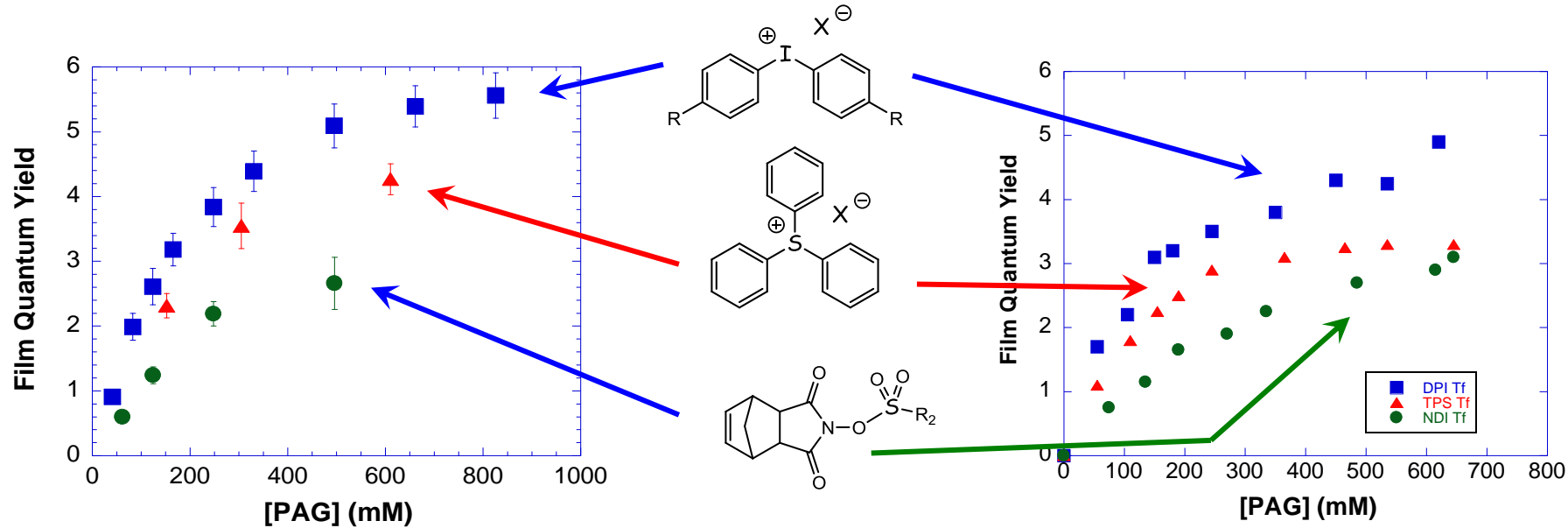


Electron-PAG Reaction Efficiency



II. PAG Reaction Mechanisms in EUV

2008: Is it possible to "Titrate" the number of e- using PAG?



Prior work also showed iodine based PAG more efficient than sulfur

Higgins & Brainard¹
Max H⁺ Φ = 5.6

Kozawa & Tagawa²
Max H⁺ Φ = 4.9

- Two PAG-Loading studies agree: Quantum Yields of 5-6 H⁺/Photon are possible.
- Higher Quantum Yield gives better Z-Parameter¹

1. Higgins & Brainard SPIE 2008 and JJAP 2011 V. 50
 2. Kozawa & Tagawa JJAP 2010 V. 49

Brainard 2013 SPIE

Future Work

- Incorporate penetration depth to calculate cross-sections, not just reactions per electron for each PAG
- Incorporate electron backscattering measurements to the raw data to improve accuracy of results
- Gather data at lower electron energies
- Expand study to non-ionic PAGs and PAGs with non-benzene outgassing products

Acknowledgements

Project Funding By:



Accelerating the next technology revolution.

**Brainard and
Denbeaux Groups:**

Ryan Del Re

Jodi Hotalen

Mihirkant Upadhyaya

**DuPont Electronic Materials:
Supplying Polymers**



Accelerating the next technology revolution.